

<b>Notice of References Cited</b>	Application/Control No. 10/683,727		Applicant(s)/Patent Under Reexamination SHERMAN, ARTHUR	
	Examiner KELLY STOUFFER		Art Unit 1792	Page 1 of 1

#### U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
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#### FOREIGN PATENT DOCUMENTS

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#### NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Catherine et al. Plasma Deposition of Aluminum Oxide Films, J. Elec. Mat. 17(2), 1988, pp 127-134.
	V	Ehle et al. Low Temperature Aluminum Oxide Deposition Using Trimethylaluminum, J. Elec. Mat, 12(3), 1982, pp 587-601.
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\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
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